



DFW

PATENT
Customer No. 22,852
Attorney Docket No. 04329.3247-00

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
KATSUYUKI SEKINE ET AL.)
Application No.: 10/785,074) Group Art Unit: 2823
Filed: February 25, 2004) Examiner: W. M. Brewster
For: SEMICONDUCTOR DEVICE AND) Confirmation No.: 8935
MANUFACTURING METHOD)
THEREOF)

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

RESPONSE TO RESTRICTION REQUIREMENT

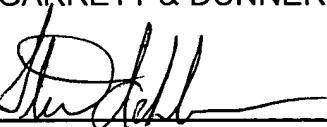
In a restriction requirement mailed October 13, 2005, the period for response to which extends through November 14, 2005 (November 13 being a Sunday), the Examiner required restriction under 35 U.S.C. § 121 between Group I (claims 1-9), characterized by the Examiner as being drawn to means for controlling surface effects including three or more insulating layers; and Group II (claims 10-20), characterized by the Examiner as being drawn to silicon oxide formation with wave energy. Applicants elect to prosecute Group II (claims 10-20), without traverse.

Please grant any extensions of time required to enter this response and charge any additional required fees to our deposit account 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW,
GARRETT & DUNNER, L.L.P.

Dated: November 10, 2005

By: 
Steven L. Ashburn
Reg. No. 56,636